

Nathaniel E Richey

List of Publications by Year in descending order

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Version: 2024-02-01

12
papers

283
citations

1307594

7
h-index

1199594

12
g-index

12
all docs

12
docs citations

12
times ranked

452
citing authors

#	ARTICLE	IF	CITATIONS
1	Understanding chemical and physical mechanisms in atomic layer deposition. <i>Journal of Chemical Physics</i> , 2020, 152, 040902.	3.0	143
2	Mechanistic Study of Nucleation Enhancement in Atomic Layer Deposition by Pretreatment with Small Organometallic Molecules. <i>Chemistry of Materials</i> , 2020, 32, 315-325.	6.7	32
3	Role of Precursor Choice on Area-Selective Atomic Layer Deposition. <i>Chemistry of Materials</i> , 2021, 33, 3926-3935.	6.7	30
4	<i>N,N</i> -Disubstituted- <i>N</i> - α -acylthioureas as modular ligands for deposition of transition metal sulfides. <i>Dalton Transactions</i> , 2018, 47, 2719-2726.	3.3	16
5	Modified atomic layer deposition of MoS ₂ thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2020, 38, .	2.1	14
6	Aerosol-assisted chemical vapor deposition of WS ₂ from the single source precursor WS(S ₂)(S ₂ CNEt ₂) ₂ . <i>Chemical Communications</i> , 2017, 53, 7728-7731.	4.1	13
7	Molecular Layer Deposition of a Hafnium-Based Hybrid Thin Film as an Electron Beam Resist. <i>ACS Applied Materials & Interfaces</i> , 2022, 14, 27140-27148.	8.0	11
8	Elucidating the Reaction Mechanism of Atomic Layer Deposition of Al ₂ O ₃ with a Series of Al(CH ₃) _x Cl _{3-x} and Al(C _y H _{2y+1}) ₃ Precursors. <i>Journal of the American Chemical Society</i> , 2022, 144, 11757-11766.	13.7	8
9	Synthesis and Characterization of Tungsten Nitrido Amido Guanidinato Complexes as Precursors for Chemical Vapor Deposition of WN _x C _y Thin Films. <i>European Journal of Inorganic Chemistry</i> , 2018, 2018, 46-53.	2.0	5
10	Multi-metal coordination polymers grown through hybrid molecular layer deposition. <i>Dalton Transactions</i> , 2021, 50, 4577-4582.	3.3	5
11	Understanding and Utilizing Reactive Oxygen Reservoirs in Atomic Layer Deposition of Metal Oxides with Ozone. <i>Chemistry of Materials</i> , 2022, 34, 5584-5597.	6.7	4
12	Methyl-methacrylate based aluminum hybrid film grown via three-precursor molecular layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2022, 40, 023405.	2.1	2